Wavefunction-Engineering of the Optoelectronic Yield for Intersubband THz-Laser Nanodevices

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Abstract

A novel THz-luminescence LASER nanoheterostructure of the intersubband, longer-wavelength limit, mid-infrared functionality type is designed on the basis of optically pumped dual resonant tunnelling of conductivity electrons within an appropriately energetically determined scheme of five subbands hosted by two communicating asymmetric approximately rectangular quantum wells (QWs).

The upper LASER action level employed is the second excited subband of the nanostructure back, wider QW and is being provided with electrons via resonant tunnelling from the first excited subband of the nanostructure front QW being populated through remotely ignited optical pumping out of the local fundamental subband.

As the lower LASER action level, on the other hand, functions the first excited back QW subband, directly delivering the received electrons to the local fundamental subband – via a fast vertical longitudinal optical phonon scattering-, wherefrom they are being recycled back to the nanostructure front QW fundamental subband by virtue of a second – reverse sense – resonant tunnelling – mediated normal charge transport mechanism.

LASER action level population inversion and intersubbad transition (ISBT) effective dipole lengths are critically monitored in connexion to the pertinent ISBT oscillator strengths and device stimulated optical gain achievable.

I. Introduction

The investigation of semiconductor heterointerfaces is a prominent subject of ongoing research in view of the crucial importance which they possess for the functionality of numerous optoelectronic microdevices [1-6].

For more than two decades, the designing strategy of wavefunction-engineering [7] has systematically been giving birth to an admirable wealth of innovative semiconductor devices offering a high degree of tunability in their optoelectronic performance.

Celebrated pioneering microelectronic heterostructures of the kind have been the Bloch oscillator [8, 9], the resonant tunnelling double heterodiode [10], the hot electron tunnelling transistor [11], and the revolutionary quantum cascade LASER [12, 13].

In the present Paper, the principle of operation of an intersubband, far mid-infrared unipolar LASER action heterosturcture based on optically pumped dual resonant tunnelling between two both spatially and energetic depth – wise asymmetric quantum wells (QWs) is outlined in terms of band gap engineering and quantum mechanical conductivity electron vertical transport and local energetic transition functionality.

The required LASER action population inversion level is monitored via a rate equation formalism against the ratio of the crucial time constants characterising the two successive resonant tunnelling processes involved along with the intervening intersubband longitudinal optical phonon scattering. A generic application of the operational principle to a model four-semiconductor nanostructure predictably emitting in the 20 µm far mid infrared coherent electromagnetic radiation spectrum band is discussed, with a measure of designed the nanodevice optoelectronic yield given by the intersubband stimulated optical gain, expressible through the LASER action population inversion in terms of the subband lifetimes entailed.

Wavefunction-Engineering

The present Paper aims at proposing a novel LASER action nanoheterosturcture [14] operational principle based on remotely optically pumped [15, 16] dual resonant tunnelling (OPRT) unipolar change transport mechanism materialisable within the framework of two communicating quatum wells (CQWs), asymmetric both in the their spatial extension and energetic barrier height aspect, hosting a total of five partially localised subbands two (the fundamental If> and first excited If '>) on the part of the envisaged device front [F] QW and the remaining three (the fundamental Ib>, the first excited Ib'>, and the second excited Ib">) on the other part, of the OPRT device back [B] QW-, a band gap engineering designing meant to have established two selective. achievable by a nanostructure respective growth procedure, energy matchings; one between the uppermost subbands If '> and Ib"> of the two COWs and another concerning the two neighbouring OWs innermost fundamental sublevels If > and Ib> (Figure 1).

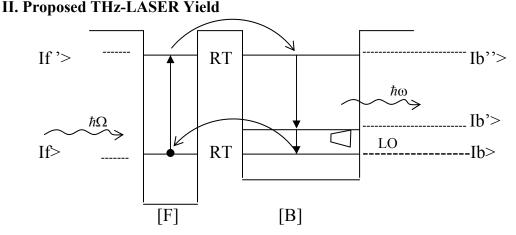


Figure 1. Wavefunction-engineering of the proposed THz-LASER.

The two LASER action OPRT nanodevice levels are designed to be the second excited Ib"> back [B] QW subband and the local next lower first excited Ib'> one:

The upper OPRT LASER action level is predicted to be being provided with conductivity electrons resonantly tunnelling [17, 18] into it out of its energetically matched device front [F] QW first excited If '> subband, being populated through remotely ignited optical intersubband pumping from its local fundamental If>, front OW, subband. The lower OPRT nanostructure LASER action level is, on the other hand, expected to be directly delivering its radiatively de - excited electrons to the local, device back [B] QW, fundamental Ib> subband via a particularly fast longitudinal optical (LO) phonon scattering, almost vertical in the reciprocal space, favoured by a band gap - engineered energetic proximity of the entailed

$$\frac{\mathrm{dN}_{\mathrm{Ib}''\succ}}{\mathrm{dt}} = \frac{1}{\mathrm{T}_{\mathrm{FB}}} \mathrm{N}_{\mathrm{If}'\succ} - \frac{1}{\tau_{\mathrm{Ib}''\succ}} \mathrm{N}_{\mathrm{Ib}''\succ}$$
$$\frac{\mathrm{dN}_{\mathrm{Ib}'\succ}}{\mathrm{dt}} = \frac{1}{\tau} \mathrm{N}_{\mathrm{Ib}''\succ} - \frac{1}{\tau_{\mathrm{Ib}'\succ}} \mathrm{N}_{\mathrm{Ib}'\succ}$$

with $N_{If} >$, $N_{Ib} >$ and $N_{Ib} >$ sheet being the electron concentration of nanostructure resonator level If '>, Ib'> and Ib''>, 1 being respectively, the temporal rate of achieving the resonant tunnelling charge transport from the [F] QW first excited subband If '> onto the energetically commensurate [B] QW second **Ib'>** \leftrightarrow **Ib>** intersubband separation with the characteristic LO phonon energy valid under the device operational conditions entailed within the [B] QW semiconductor material.

considered OPRT The LASER nanostructure resonant microcavity functionality [19, 21] is, furthermore, determined by the above LO phonon scattering of down converted radiatively _ conductivity electrons (from the LASER action lower level to the local [B] QW fundamental subband) being succeeded by their being recycled back to the OPRT LASER nanostructure [F] QW fundamental If> subband by virtue of a second – reverse sense – resonant tunnelling – mediated normal charge transport mechanism.

The rate equation modelling of the LASER action functionality of subband levels Ib''> and Ib'> is taken of the form:

$$\frac{\mathbf{b}''_{\succ}}{\mathbf{b}'} = \frac{1}{\mathbf{T}_{\mathrm{FB}}} \mathbf{N}_{\mathrm{If}'\succ} - \frac{1}{\tau_{\mathrm{Ib}''\succ}} \mathbf{N}_{\mathrm{Ib}''\succ}$$
(1),
$$\frac{\mathbf{b}'_{\succ}}{\mathbf{b}'} = \frac{1}{\tau} \mathbf{N}_{\mathrm{Ib}''\succ} - \frac{1}{\tau_{\mathrm{Ib}'\succ}} \mathbf{N}_{\mathrm{Ib}'\succ}$$
(2),

excited subband Ib''>, $\tau_{Ib''>}$ being the total lifetime of upper LASER action level Ib" > - expressible by means of the combined radiative and nonradiative $Ib'' \rightarrow Ib' \rightarrow down$ conversion rate $\frac{1}{\tau}$ and the non – radiative direct Ib''> \rightarrow Ib> relaxation rate $\frac{1}{\tau_{Ib'' \succ \rightarrow Ib \succ}}$ as

$$\frac{1}{\tau_{Ib''\succ}} = \frac{1}{\tau} + \frac{1}{\tau_{Ib''\succ \to Ib\succ}}$$

and $\frac{1}{\tau_{Ib'\succ}}$ being the non –

radiative, fast vertical longitudinal optical phonon scattering rate of electrons received by the lower LASER action subband Ib'> to the

local, [B] QW, fundamental subband Ib>.

(1) and (2) form a system in five unknowns, namely $N_{Ic>}$ (c = f, f', b, b', b'') – the areal electron densities of the five nanostructure resonator levels Ic> -, along with the following equations:

$$\frac{dN_{If\succ}}{dt} = \frac{1}{T_{BF}} N_{Ib\succ} - \frac{I\Sigma}{\hbar\Omega} N_{If\succ}$$
(4),
$$\frac{dN_{If'\succ}}{dt} = \frac{I\Sigma}{\hbar\Omega} N_{If\succ} - \frac{1}{T_{FB}} N_{If'\succ}$$
(5),

$$\frac{\mathrm{dN}_{\mathrm{Ib}\succ}}{\mathrm{dt}} = \frac{1}{\tau_{\mathrm{Ib}'\succ\to\mathrm{Ib}\succ}} \mathrm{N}_{\mathrm{Ib}'\succ} + \frac{1}{\tau_{\mathrm{Ib}'\succ}} \mathrm{N}_{\mathrm{Ib}'\succ} - \frac{1}{\mathrm{T}_{\mathrm{BF}}} \mathrm{N}_{\mathrm{Ib}\succ}$$
(6),

where $\frac{1}{T_{BF}}$ denotes the temporal rate

at which the (reverse sense) Ib> \rightarrow If> resonant electron tunnelling is effected within the CQWs, I the optical pumping intensity, Ω the pumping photon cyclic frequency, and Σ the optical absorption cross

$$Y = \frac{1}{L} \sigma \Delta N$$

with L being the spatial extension of the entire CQWs configuration, σ the LASER stimulated emission cross section, for producing the secondary, coherent photons (of energy $\hbar\omega = \Delta E_{Ib' \succ \to Ib' \succ} = \Delta E$), and ΔN the LASER action population inversion between levels Ib''> and Ib'> obtained from the above electron concentration rate equation system solved at the steady state of the concurrency of the different charge section exhibited by electrons initially resting upon [F] QW fundamental subband level If> to incoming pumping photons.

On the other hand, the quantum mechanically thus designed stimulated optical yield Y is determined as [15]

(7),

transport mechanisms within the OPRT nanoheterostructure.

The aforementioned model formalism employed – based upon the rate equation monitoring of the proposed OPRT LASER action level population evolution and inversion – incorporates the transmission coefficient determination [14, 17] for the resonant tunnelling inter – QW communication mechanism consecutive steps.

III. Model Application of the Proposed OPRT LASER

For studying the applicability of the herewith proposed optically pumped dual resonant tunnelling LASER action unipolar charge mechanism we now transport consider indicative an generic semiconductor nanoheterostructure based on the conventional Al_xGa_{1-x} As/GaAs material system.

In particular, we employ two totally asymmetric - both in the spatial width and in the energetic barrier height –, communicating through an intervening barrier layer, approximately rectangular quantum wells. both formulated within (different portions of) the GaAs semiconductor: The front QW [F] of spatial width 96 °A and energetic barrier height 221 meV, contained between a surface Al_{0.3} Ga_{0.7} As slab and the inter - QW communication barrier layer, and the back QW [B] of growth axis extension 162 °A and energetic confinement hill 204 meV, spanning the region between the inter - QW communication barrier layer and a botton Al 0.33 Ga0.67 As slab. The intervening, inter – OW communication barrier layer may non – exclusively be regarded as the succession (either abrupt or graded) of two rather equithick sublayers of Al_{0.3} $GA_{0.7}$ As and Al_{0.33} $Ga_{0.67}$ As.

The major goal attempted by the above employment is the establishment of a specific band gap engineering depicting the desired novelty of *double* (both spatial *and* energetic trench – wice) asymmetry between the two successive

Functionality and Yield Designing to a Generic Nanostructure and Discussion

communicating QWs embodying the crucial nanostructure hosting the prescheduled five in all conduction subbands fulfilling the dual energy matching (both between the uppermost energy levels of the two QWs and between the lowest two, fundamental, subbands of theirs) needed for the possibility of the (optically ignited) dual resonant tunnelling inter QW communication.

For the computational technique utilised for self consistently depicting the energy eigenvalues above, the Sturm -Liouville eigenuvalue problem comprising the quantum mechanical Schroedinger differential equation and the appropriate exact boundary conditions conjugate with the eigenfuction entailed vanishing asymptotically at infinities is treated by the finite difference method after the employment of an independent variable transformation restricting the integration domain to the finite, universal, dimensionless interval [-1, 1]. The handling of the problem the evolves into numerical calculation of the eigenvectors and respective eigenvalues of a specific tridiagonal matrix hosting the three successions of coefficients appearing in the kind of finite difference equations selected to convergingly approach the initial Strum Liouville differential equation [22].

With respect to the generic situation of a conductivity electron being hosted by the quantum well (QW) of potential energy profile U(x) against the growth axis coordinate x within a conventional semiconductor nanodevice heterointerface, pertinent the Schrödinger equation, concerning the electron de Boglie time – independent wavefunction ψ (x) and taking into account the spatial variation m^{*} (x) of the carrier effective mars, reads:

$$-\frac{d}{dx}\left[\frac{\hbar^2}{2m^*(x)} \frac{d\psi(x)}{dx}\right] + U(x)\psi(x) = E\psi(x),$$
(8)

with E being the allowed energy eignevalue conjugate to each physically meaningful wavefunction $\psi(x)$, solving (8) and vanishing asymptotically at infinities,

and \hbar being Planck's action constant divided by 2π .

Performing, now, an independent variable transformation, namely,

$$\chi \equiv \alpha x^* \operatorname{Arctanh}(\xi) \leftrightarrow \varphi(\xi) \equiv \psi[x(\xi)],$$
(9)

we obtain in place of (8) the Sturm – Liouville differential equation

$$\frac{d}{d\xi} \left[\mu(\xi) \frac{d\varphi(\xi)}{d\xi} \right] - \upsilon(\xi)\varphi(\xi) + \lambda\sigma(\xi) \varphi(\xi) = 0,$$
(10)

under the boundary conditions

 $\varphi(-1) = 0 \& \varphi(+1) = 0,$ (11)

with functions $\mu(\xi), \upsilon(\xi)$ and $\sigma(\xi)$ in the new dimensionless variable ξ (belonging to the universal interval [-1, +1]) defined as

$$\mu(\xi) = \frac{1}{\alpha} (1 - \xi^2) \frac{m_o}{m^*[x(\xi)]}, (12)$$

$$v(\xi) = \frac{2\alpha}{1 - \xi^2} \frac{U[x(\xi)]}{E^*},$$
 (13)

$$\sigma(\xi) \equiv \frac{2\alpha}{1 - \xi^2},\tag{14}$$

and dimensionless new, "reduced energy", eigenvalue λ defined as

$$\lambda = \frac{E}{E^*},\tag{15}$$

where E^* denotes a convenient energy scale

$$E^* = \frac{\hbar^2}{m_0 x^{*2}} = 1 e V,$$
 (16)

rendering the characteristic confinement length x^* entering the independent variable transformation (9) after the dimensionless scale factor α equal to 2.76043 $\stackrel{0}{\text{A}}$, m_o giving the electron rest mass.

For converting the Sturm – Liouville differential equation concerning the nanoheterointerface two-dimensional electron gas (2DEG) transformed wavefunction $\varphi(\xi)$ into a linearised $\mu_{i\cdot\frac{1}{2}}(\frac{\phi_{i}-\phi_{i\cdot 1}}{k})],$

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system of difference equations, we employ the numerical approximation

 $\frac{d}{d\xi} [\mu(\xi) \frac{d\phi(\xi)}{d\xi}] \rightarrow \frac{1}{k} [\mu_{i+\frac{1}{2}} (\frac{\phi_{i+1} - \phi_i}{k}) - \frac{1}{k} [\mu_{i+\frac{1}{2}} (\frac{\phi_{i+1} - \phi_i}{k}) - \frac{1}{k} (\frac{\phi_{i+1} - \phi_i}{k}) - \frac{1}{k} [\mu_{i+\frac{1}{2}} (\frac{\phi_{i+1} - \phi_i}{k}) - \frac{1}{k} (\frac{\phi_{i+$

(17)

in which the computational (nodal

and interstitial, respectively) grid

points ξ_n (whence $f_n \equiv f(\xi_n)$ with f

standing for function φ , μ , υ , and σ ,

as the case might be) are chosen as

$$\phi_0 = \phi(\xi_0) = \phi(-1) = 0$$

&

$$\phi_{N+1} = \phi(\xi_{N+1}) = \phi(-1 + (N+1)\frac{2}{N+1}) = \phi(+1) = 0.$$
(20)

The Schrödinger equation eigenvalue problem is, thus, approximated by the system of difference equations

$$\{\alpha_i\phi_{i-1} + \beta_i\phi_i + \gamma_i\phi_{i+1} = -k^2\Lambda\phi_i; i = 1, 2, ..., N\}$$
(21)

or, equivalently, in tridiagonal matrix rows form,

$$\begin{aligned} \xi_{i} &= -1 + ik \ (i = 0, 1, 2, ..., N + 1), \\ \xi_{i \pm \frac{1}{2}} &= \xi_{i} \pm \frac{k}{2} \ (i = 1, 2, ..., N + 1), \end{aligned}$$
(18)

for a uniform grid spacing $k = \frac{1 - (-1)}{N + 1} = \frac{2}{N + 1},$ (19)

and for which the adjoint boundary conditions become, after (5) & (12),

$$\{\sum_{j=1}^{N} \{ [\alpha_{i}\delta_{i-1,j} + \beta_{i}\delta_{i,j} + \gamma_{i}\delta_{i+1,j}]\phi_{j} \} = -k^{2}\Lambda\phi_{i} ; i = 1, 2, ..., -k^{2}\Lambda\phi_{i} ; i=1, 2, ..., N \}$$
(22)

 $(\delta_{i,j}$ being the Kronecker delta), with the sets of coefficients $\alpha_i, \beta_i, \gamma_i$ defined as

$$\alpha_{i} = \frac{\mu_{i-\frac{1}{2}}}{\sigma_{i}}, \gamma_{i} = \frac{\mu_{i+\frac{1}{2}}}{\sigma_{i}}, \beta_{i} = -(\alpha_{i} + \gamma_{i} + \frac{k_{i}v_{i}}{\sigma_{i}}); i = 1, 2, ..., N,$$
(23)

and Λ denoting the approximation to the exact reduced energy eigenvalue λ (E_q. (15)), produced by the constructed numerical algorithm and expected to more closely converge to it with increasing number N of computational grid nodal points ξ_i utilised.

The treatment has, therefore, evolved into the matrix eigenvalue problem

$$\{\sum_{j=1}^{N} \{\Lambda_{i,j}\phi_{j}\} = -k^{2}\Lambda\phi_{i}; i = 1, 2, ..., N\},\$$

(24)

with the N-th order square tridiagonal matrix

$$\{(\Lambda_{i,i}; j=1,2,...,N); i=1,2,...,N\}$$

defined by

$$\Lambda_{i,j} \equiv \alpha_i \delta_{i-1,j} + \beta_i \, \delta_{i,j} + \gamma_i \, \delta_{i+1,j}.$$
(25)

Indeed; the opposite of the eignvalues of matrix $\{\Lambda_{i,j}\}$ divided by k^2 give Λ , the approximations to the heterointerface wavefunction

exact reduced energy eigenvalues λ , thus computing $(E_q.(15))$ the allowed QW 2DEG subband energies E = λE^* . Obviously, given that the general Strum - Liouville system (10) may admit an infinite sequence eigenvalues λ, of the finite succession of N eigenvalues Λ for algorithmic matrix $\{\Lambda_{i,j}\}$ provides the numerical approximations to only the N lowest true reduced energy eigenvalues λ , a slightly lessening approximation sufficiency for the last higher order computed eigenvalues being algorithmically probable. On the other hand, the N determined, Strum – Liouville eigenvectors $|\phi(\xi)\rangle$ conjugate to these numerical eigenvalues Λ unveil through transformation (9) the quantum mechanically allowed wavefunctions ψ (x) for the 2DEG dwelling within the nanodevice heterointerface QW underlying crucial and the optoelectronic effects exhibited by semiconductor the generic nanostructure. In particular, such a determination of the nanoheterointerface 2DEG wavefunction to the may lead computation of its entailed penetration length into the nanodevice neighbouring energy barrier layer, thus facilitating the prediction of 2DEG mobility behaviour parameterised by the order of wavefunction excitation and, furthermore, the consideration of quantum mechanical tunnelling transmission probability for conductivity electrons escaping the heterointerface and travelling through the nanodevice – by virtue of normal transport mechanism a advantageously exploitable, especially at nanoelectronic cryogenic ambient temperatures.

In this manner, the partially conductivity electron localised eignestates accommodated by the couple of communicating QWs in the model application under study correspond to the energy eigenvalues (measured within each QW from its energetic bottom upwards): E (If>) = 32 meV, E (If '>) = 136 meV - forthe front QW fundamental and first excited bound state, respectively, and E (Ib>) = 14 meV, E (Ib'>) = 55 meV, and E (Ib''>) =121 meV – for the back OW fundamental, first excited, and second excited bound state, respectively.

Notably, against this predicted energy eigenvalue configuration, the fundamental back QW eigenstate Ib> elevated by 14 meV over the back QW energetic botton finds itself well aligned with the conjugate fundamental eigenstate If> of the front QW raised above its QW energetic botton by an amount corresponding to the inter - QW energetic bottom discrepancy plus, about, the former fundamental eigenstate Ib> height over its local QW bottom.

In an analogous manner, the uppermost bound eigenstates of the two communicating QW, emerge aligned, as the difference in the height of each over its local QW bottom almost cancels the energetic height asymmetry of the two QW bottoms.

The ensuing calculations incorporate the determination of the effective dipole lengths associated with the intersubband transitions collaborating or antagonising with another through one the optoelectronic structure, an intersubband transition lifetime engineering thus emerging as a conformal mapping of the original heterosturcture wavefunctionengineering attempted. The determined intersubband transition (ISBT) effective dipole lengths, furthermore, demonstrate the oscillator strengths supporting the different ISBT events, whereas the LASER action population inversion predicted leads to the device stimulated optical gain.

preliminary Our results (radiative transition time constant around 45 ns, corresponding to an ISBT dipole length $\langle b'' | z | b' \rangle$ around 1 nm), trace a LASER far mid - infrared emission OPRT functionality in the 65 meV / 15 THz range, with a stimulated optical gain Y sensitivity $\frac{\partial Y}{\partial I}$ to the pumping illumination power Ι around $11 \frac{\text{cm}^{-1}}{10^5 \,\text{W}/\,\text{cm}^2}$.

References

[1] J.J. Harris, R. Murray, and C. T. Foxon, Semicond. Sci. Technol. **8**, 31 (1993).

[2] Shengs S. Li, M. Y. Chuang, and L. S. Yu, Semicond. Sci. Technol. **8**, S406. (1993).

[3] L. V. Logansen, V. V. Malov, and J. M. Xu, Semicond. Sci. Technol. **8**, 568. (1993).

[4] C. Juang, Phys. Rev. B 44, 10706 (1991).

[5] M. Ya. Asbel, Phys. Rev. Lett. **68**, 98 (1992).

[6] G. J. Papadopoulos, J. Phys. A. **30**, 5497 (1997).

[7] F. Capasso and A. Y. Cho, Surf. Sci. **299/300**, 878 (1994).

[8] R. O. Grondin, W. Porod, J. Ho, D. K. Ferry, and G. J. Iafrate, Superlattices and Microstructures 1, 183 (1985).

[9] J. N. Churchill and F. E. Holmstrom, Phys. Lett A **85**, 453 (1981).

[10] T. C. L. G. Sollner, W. D. Goodhue, P. E. Tannenwald, C. D. Parker, and D. D. Peck, Appl. Phys. Lett. **43**, 588 (1983).

[11] N. Yokoyama, K. Imamura, T. Oshima, H. Nishi, S. Muto, K. Kondo, and S. Hiyamizu, Japan. J. Appl. Phys. **23**, L. 311 (1984).

[12] J. Faist, F. Capasso, D. Sivco, D. Sirtori, A. L. Hutchinson S. N. G. Chu, and A. Y. Cho, Science **264**, 553 (1994).

[13] J. Faist, F. Capasso, C. Sirtori, D. L. Sivco, A. L. Hutchinson, and A. Y. Cho, Electron. Lett. **32**, 560 (1996).

[14] Jasprit Singh, *Semiconductor Optoelectronics* (McGraw – Hill, New York, 1995), Chap. 10.

[15] G. H. Julien, O. Gauthier – Lafaye, P. Boucaud, S. Sauvage, J. – M. Lourtioz, V. Thierry – Mieg, and R. Phanel, *Intersubband Transitions in Quantum Wells : Physics and Devices* (Kluwer Academic Publishers, Boston, 1998), Chap. 1, Paper 2nd.

[16] E. A. Anagnostakis, Phys. Stat. Sol. B **181**, K15 (1994).

[17] G. Bastard, *Wave Mechanics Applied to Semiconductor Heterostructures* (Les Edition de Physique, Les Ulis Cedex – France, 1987), Chap. IV, VI.

[18] Wen – Huei Chiou, Hsi – Jen Pan, Rang – Chau Liu, Chun – Yuan Chen, Chith – Kai Wang, Hung – Ming Chuang, and Wen – Chau Liu, Semicond. Sci. Technol **17**, 87 (2002).

[19] M. Pessa, M. Guina, M. Dumitrescu, I. Hirvonen, M. Saarinen, L. Toikkanen, and N. Xiang, Semicond. Sci. Technol. **17**, R1 (2002).

[20] J. M. Buldu, J. Trull, M. C. Torrent, J. Garcia – Ojalvo, and Claudio R. Mirasso, J. Opt. B: Quantum Semiclass. Opt. **4**, L1 (2002).

[21] V. D. Kulakovskii, A. I. Tartakovskii, D. N. Krizhanovskii, N. A. Gippius, M. S. Skolnick, and J. S. Roberts, Nanotechnology **12**, 475 (2001).

[22] E. A. Anagnostakis, J. Non-Cryst. Sol. **354**, 4233 (2008).